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Attorney Docket No.: PATENT
SLM-05800

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#12
W. Lamm
9/15/03

In re Application of:

Robert W. Corrigan et al.

Serial No.: 09/832,738

Filed: April 10, 2001

For: **METHOD, SYSTEM AND
DISPLAY APPARATUS FOR
ENCRYPTED CINEMA**

) Group Art Unit: 2643

) Examiner:

) **TRANSMITTAL LETTER**

) 162 N. Wolfe Road
) Sunnyvale, CA 94086
) (408) 530-9700

) Customer No.: 28960

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Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: 7-16-03

By: Thomas B. Haverstock
Thomas B. Haverstock
Reg. No.: 32,571

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United States Patents or Published Patent Applications have been filed electronically (EFS ID # 43669); (EFS ID #43671); (EFS ID #43672); (EFS ID #43673); (EFS ID #43674); (EFS ID #43675); (EFS ID #43677); (EFS ID #43678); (EFS ID #43679); (EFS ID #43680); (EFS ID #43682); (EFS ID #43683); (EFS ID #43686); (EFS ID #43688); (EFS ID #43689); and (EFS ID #43690).

Applicants have become aware of the following printed publication which may be material to the examination of this application:

- U.S. Patent No. Des. 334,557;
- U.S. Patent No. Des. 334,742;
- U.S. Patent No. Des. 337,320;
- U.S. Patent No. Re. 16,767;
- U.S. Patent No. Re. 25,169;
- German Publication No. DE 32 33 195 A1;
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- European Publication No. EP 0 089 044 A2;
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- Japanese Patent Abstract JP 61-142750;
- Japanese Patent Abstract JP 61-145838;
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- Japanese Patent Abstract JP 63-305323;
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- PCT Publication No. WO 93/09472;
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- PCT Publication No. WO 93/22694;
- PCT Publication No. WO 94/09473;
- PCT Publication No. WO 94/29761;
- PCT Publication No. WO 95/11473;
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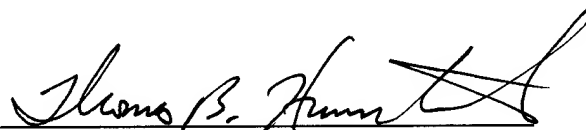
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Respectfully submitted,
HAVERSTOCK & OWENS LLP

Dated: 7-16-03

By: 
Thomas B. Haverstock
Reg. No.: 32,571

Attorneys for Applicants

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